

2011 International Workshop on EUV Lithography

**June 13-17, 2011 ■ Makena Beach Golf Resort
■ Maui, Hawaii ■**

Wednesday, June 15, 2011

Organized by



www.euvlitho.com

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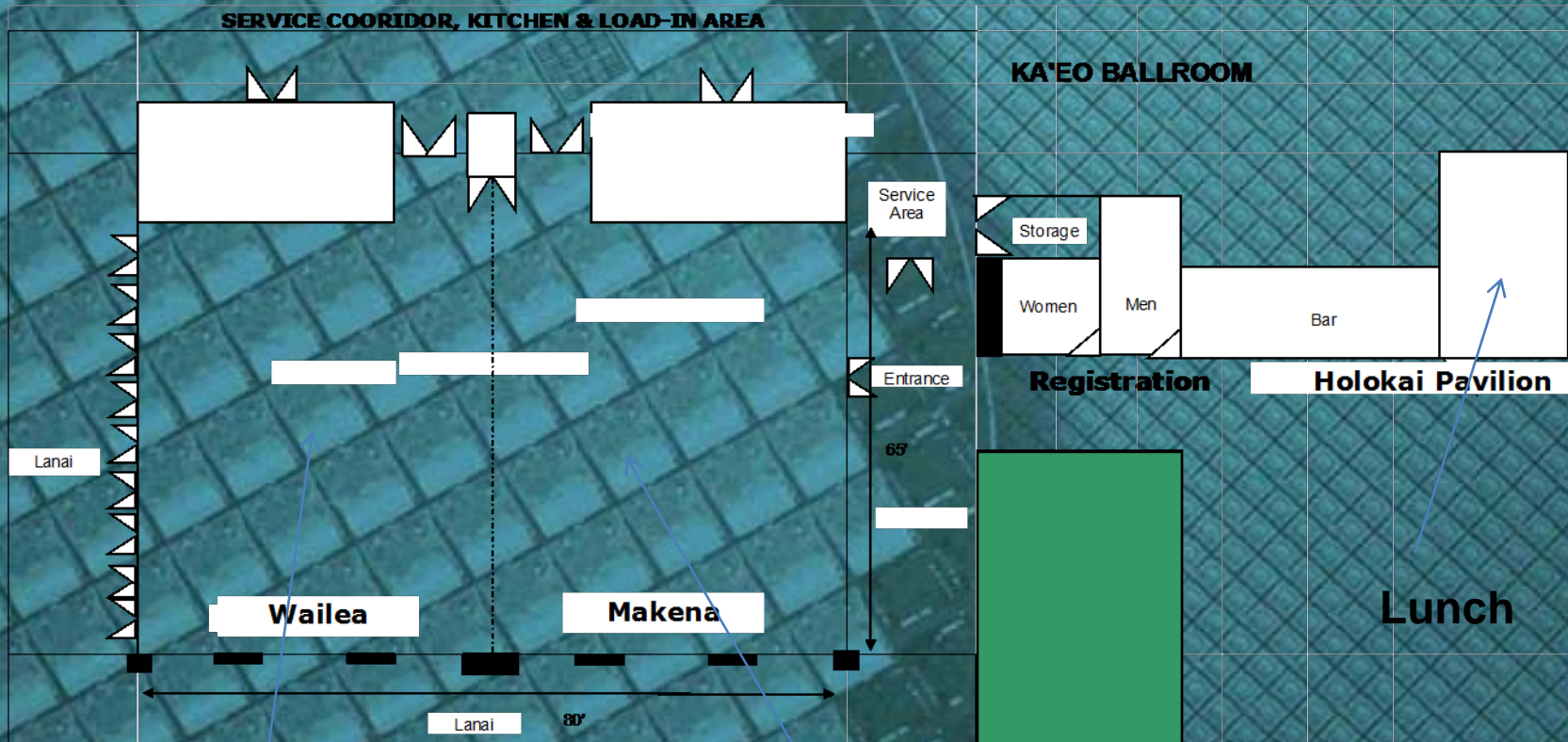
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Meeting Rooms: Makena Beach Golf Resort



General Session

Poster Session

WORKSHOP AGENDA

- **8:40 AM ...Session 1: Keynote Presentations**
- **10:00 AMBreak (15 Minutes)**
- **10:15 AM.....Business Presentation**
- **10:30 AMSession 2: Patterning**
- **11:30Lunch (45 Minutes)**
(Holokai Pavilion)

WORKSHOP AGENDA

- **12:15 PMSession 3: EUV Source Modeling**
- **12:55 PM ...Session 4: Next Generation EUV Sources**
- **1:55 PMBreak (15 Minutes)**
- **2:10 PMSession 5: EUV Sources**
- ***4:00 PM.....Adjourn for the day***